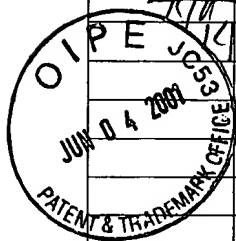


Subt. For, PTO-1449				Docket Number 100718.418 (MIC-76)		Application Number 09/652,630	
INFORMATION DISCLOSURE IN AN APPLICATION <i>(Use several sheets if necessary)</i>				Applicant David A. Cathey et al.			
				Filing Date August 31, 2000		Group Art Unit 2879	
Sheet	1	OF	1				

U.S. Patent Documents

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
KJH	5,0673,327	Nov. 5, 1991	Brodie et al.	313	402	
KJH	5,486,126	Jan. 23, 1996	Cathey et al.	445	25	



PTO
see 892

Foreign Patent Documents

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

Other Documents (Including Author, Title, Date Pertinent Pages, Etc.)

KJH	A	Guerin, L. J. et al., "SU-8 photoepoxy: A new material for FDP or PDP applications." Institute for Microsystems, Swiss Federal Institute of Technology, Switzerland, 53-54
KJH	B	Despont, M. et al., "HIGH-ASPECT-RATIO, ULTRATHICK, NEGATIVE-TONE NEAR-UV PHOTORESIST FOR MEMS APPLICATIONS," Proc. of the 10 th IEEE Int'l Workshop of Micro Electromechanical Systems (MEMS '97), Jan. 26-30, 1997, Nagoya, Japan
KJH	C	Lee, K. Y. et al., "Micromachining applications of high resolution ultrathick photoresist," J. Vac. Sci. Technol. B. 13(6), Nov/Dec 1995, pp. 3012-3016
KJH	D	Lorenz, H. et al., "Mechanical Characterization of a New High-Aspect-Ratio Near UV-Photoresist," Swiss Federal Institute of Technology, Switzerland

EXAMINER Kenneth J. Ramsey Primary Examiner	DATE CONSIDERED 4/30/03
EXAMINER: Initial if citation is considered, whether or not citation is in conformance with MPEP § 609: Draw Line through citation if not conformance and not considered. Include copy with next communication to applicant.	

